

METHOD FOR REMOVAL OF PATTERN RESIST OVER PATTERNED METAL
HAVING AN UNDERLYING SPACER LAYER

ABSTRACT OF THE DISCLOSURE

A method of removing the pattern resist that remains on a microchip wafer after etching a patterned layer that is supported by a spacer layer. After the etch, the 5 wafer is cleaned with a develop clean process that removes polymer residues from the pattern resist surface. Next is an ash to remove the hardened pattern resist surface, followed by removal of the pattern resist.